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# THE PURSUIT OF ATOMISTIC SWITCHING AND CROSS POINT MEMORY

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Intel Corporation

# Outline

- Introduction
- Problem Statement and Solution Space
- Cross Point Memory Array and Choices of Selector
- 3D XPoint Memory Technology
- Conclusion

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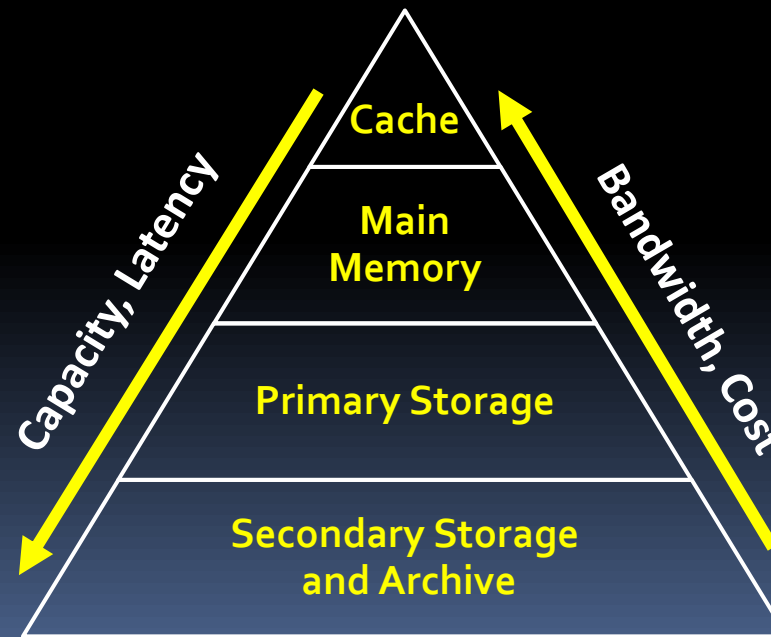
# Computer Architecture 101: Hierarchy of Memory

*each has greater capacity than the preceding but less quickly accessible*

**“The Memory Organ** – Ideally one would desire an **indefinitely large memory capacity** such that any particular ... **word** would be **immediately** ... available. ... It does not seem possible physically to achieve such a capacity. ... We are therefore forced to recognize the possibility of constructing a **hierarchy of memories**, each of which has greater capacity than the preceding but which is less quickly accessible.”

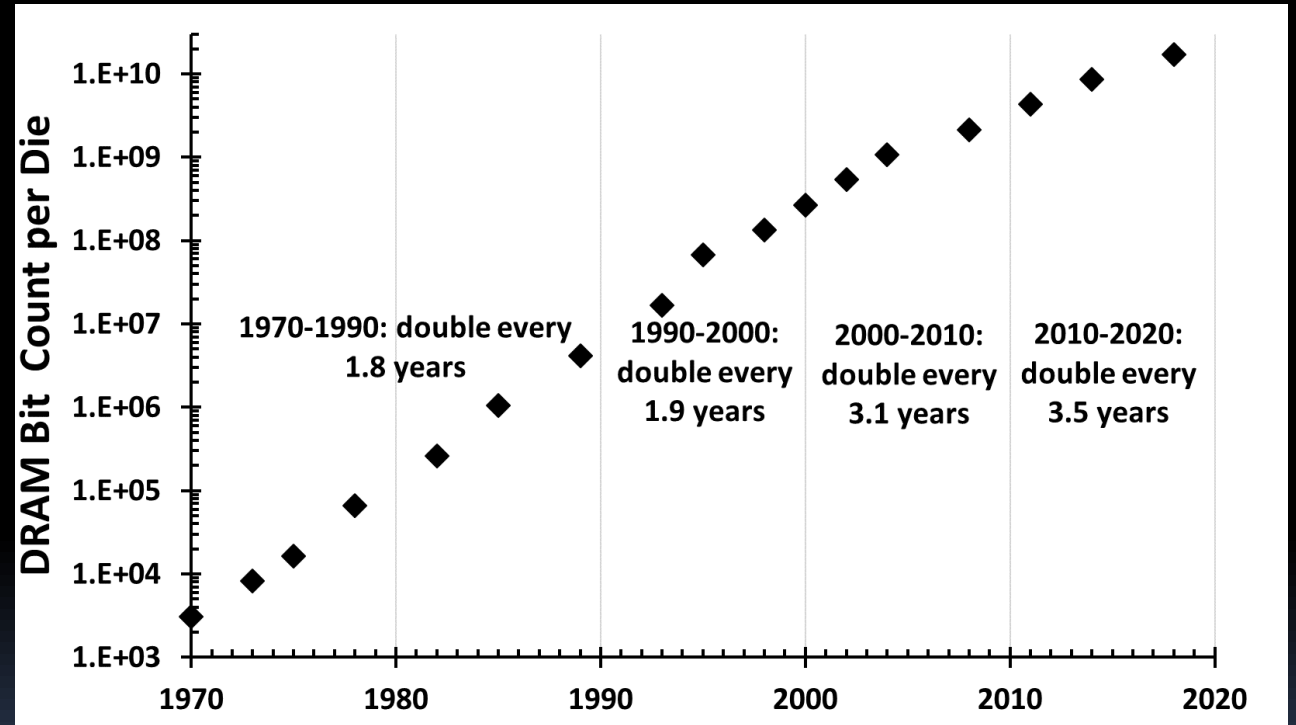
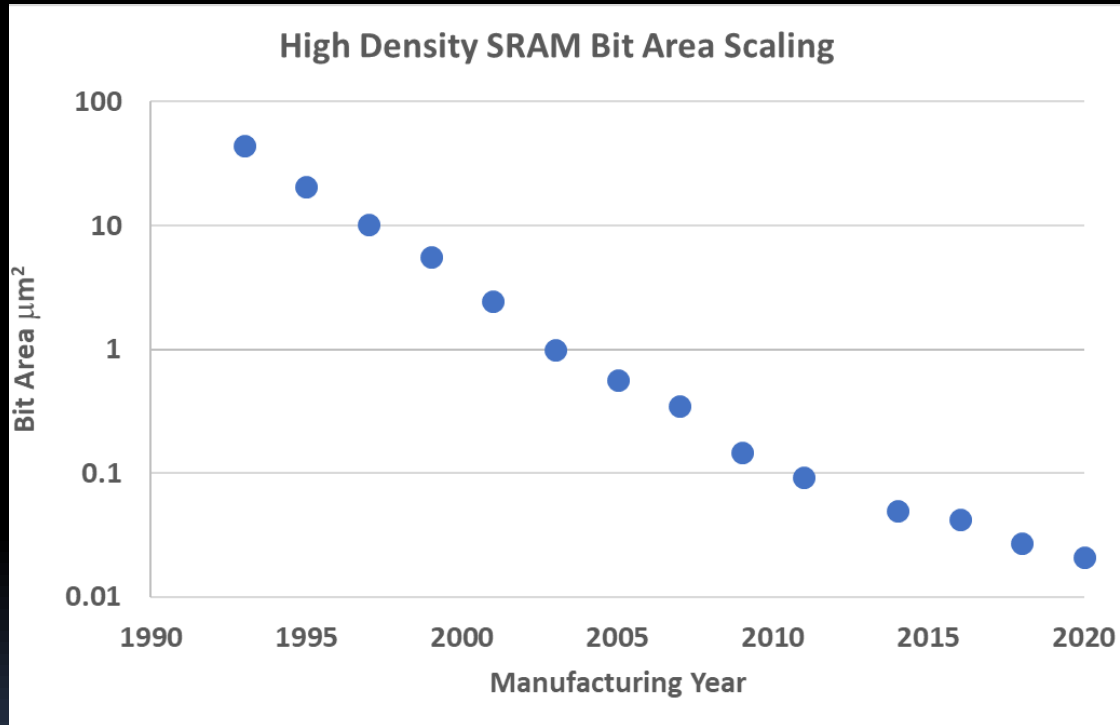
Preliminary Discussion of the Logical Design of an Electronic Computing Instrument

Arthur Burks, Herman Goldstine and John von Neumann, June/28/1946



# Cache and Main Memory Scaling

SRAM and DRAM scaling have significantly slowed

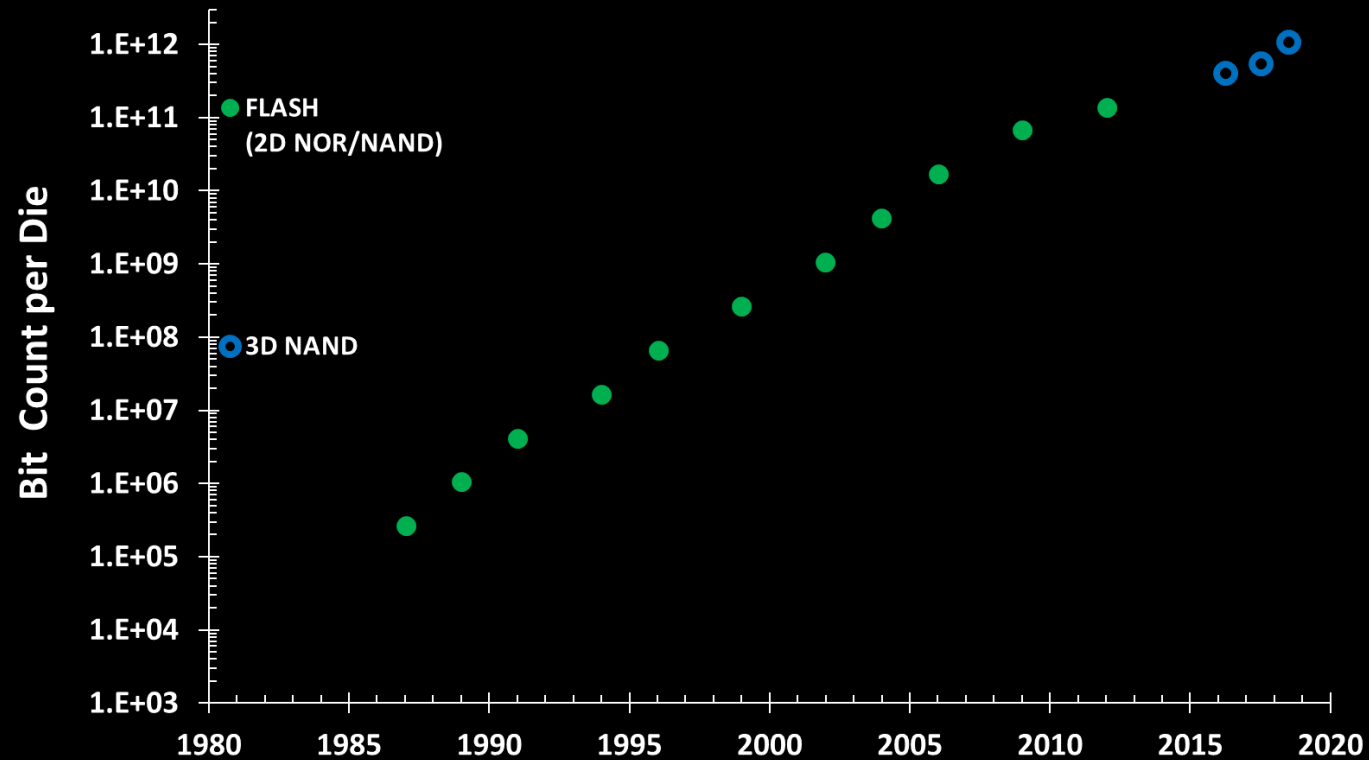


A. Fazio, "Advanced Technology and Systems of Cross Point Memory", IEDM 2020, S24.1

# Storage Scaling –

Flash based Solid State Drive displaces Hard Disk Drive\*

3D NAND warrants Cost scaling superiority for path ahead



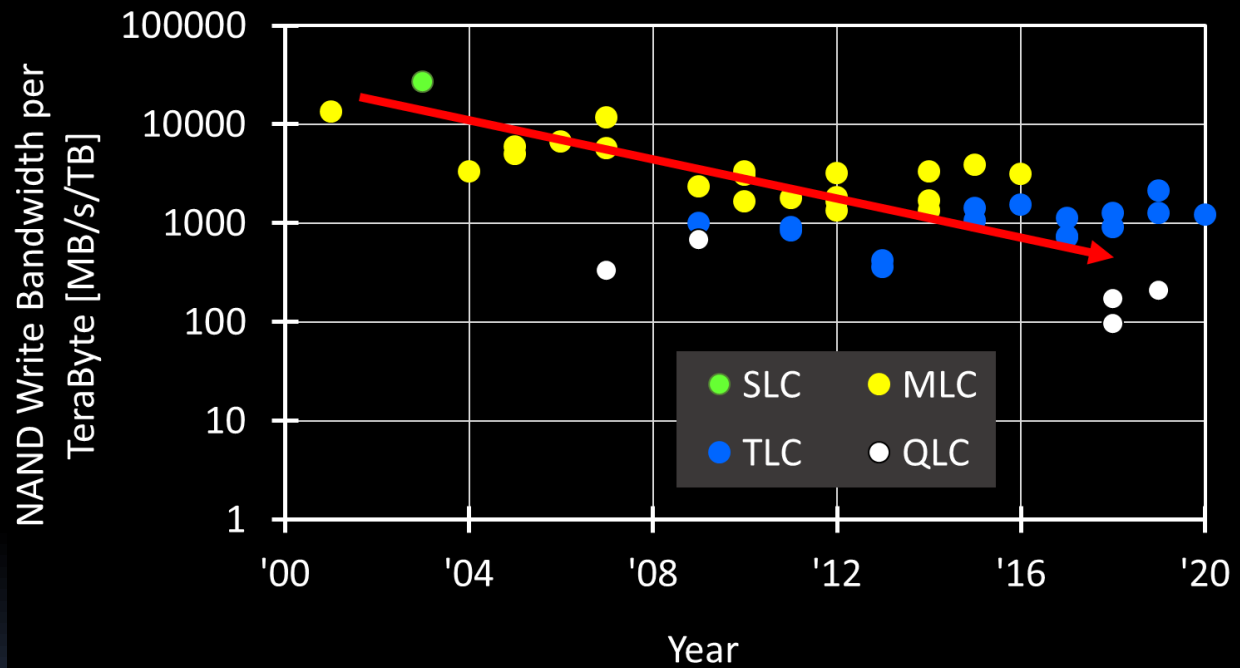
\*: Intel Ships Enterprise-Class Solid-State Drives

<https://www.intel.com/pressroom/archive/releases/2008/20081015comp.htm>

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# Storage hardly improves bandwidth without adding capacity



Source: various IEEE, ISSCC, IEDM, and IMW papers.

While capacity has grown for NAND, performance – write performance and in particular as more bits per cell are added – has not kept up with capacity growth.

As BW goals often solved by brute force (parallel die), BW density scaling becomes critical due to cost barriers. It amplifies scaling challenges.



# The anticipated solution to bridge the gap

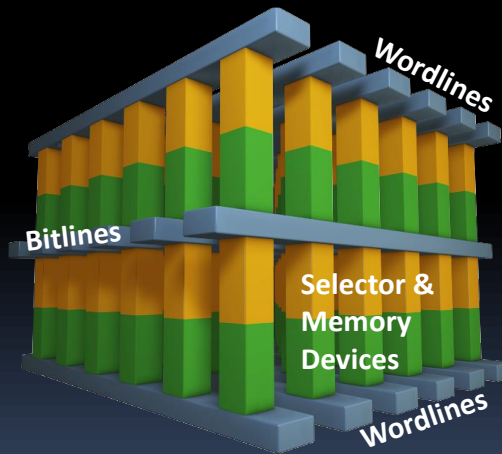
von Neumann architecture gave away the answer long ago –

*large memory capacity*

*word*

*immediately available*

## Cross Point Memory is a promising scalable solution



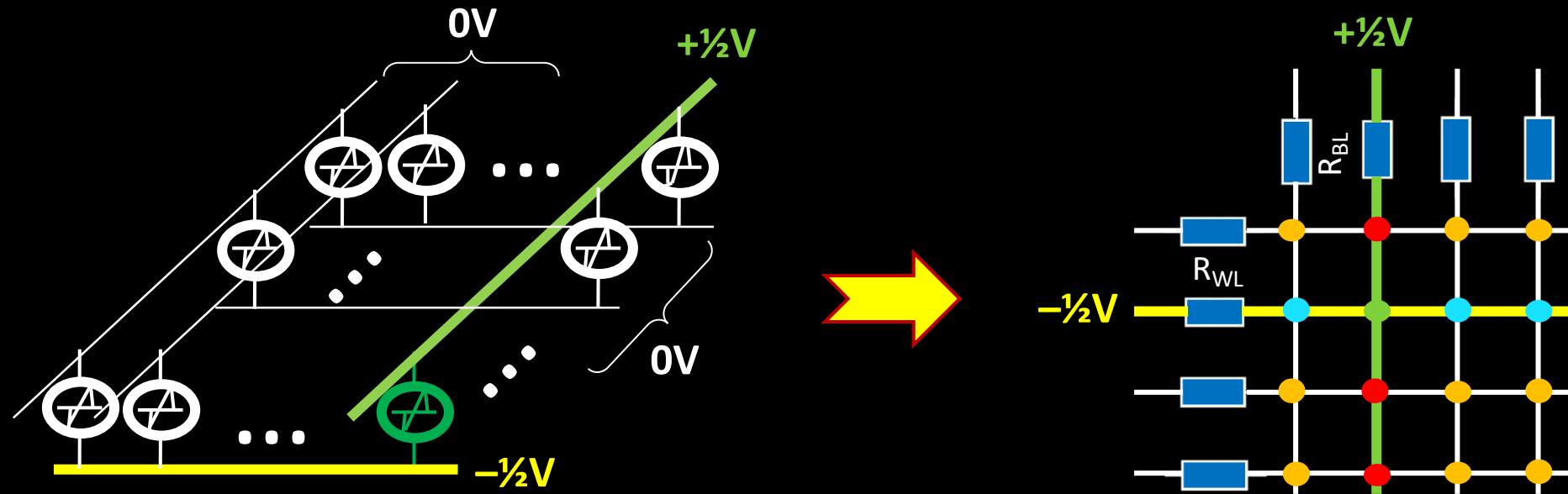
- Simple scalable structure + 3D technology  
→ Large Memory Capacity
- Individual Cell Access  
→ Word (small granularity accessible)
- Fast switching materials + low resistance metal interconnect  
→ Immediately Available

Challenge: Mating a selector device with non-linear I-V & a memory element with tight distribution

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# Cross Point Memory Array – $\frac{1}{2}$ voltage biased scheme



The selected bit (•) is at the cross point of the selected **bitline** (BL) and **wordline** (WL)

Functionality –

- A fully networked x-y resistive array → Sneak paths thru all de-selected cells (•) connect the selected BL/WL

Reliability –

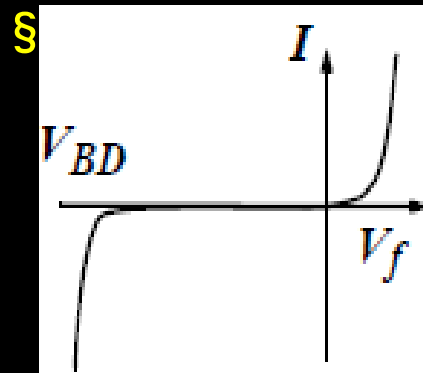
- All bits on selected BL (•) and selected WL (•) are biased → Read/Write disturbance and retention

**A selector isolates memory cells in an array, improves access accuracy and strengthens reliability.**

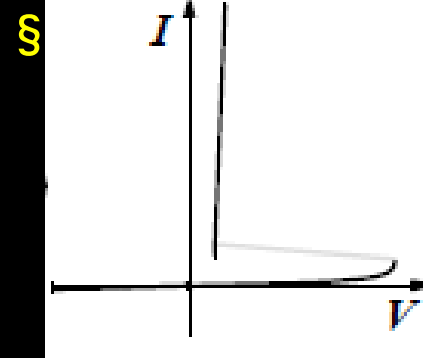
# Selector of a cross-point memory cell is a diode

**Diode:** two terminals and exhibiting a nonlinear I-V, *IEEE Standard Dictionary of Electrical and Electronics Terms, 1980*

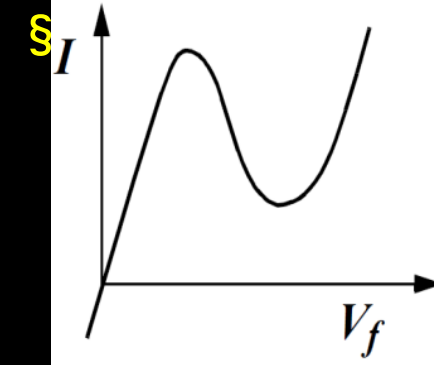
Unidirectional  
Asymmetric  
Unipolar



L-Shape

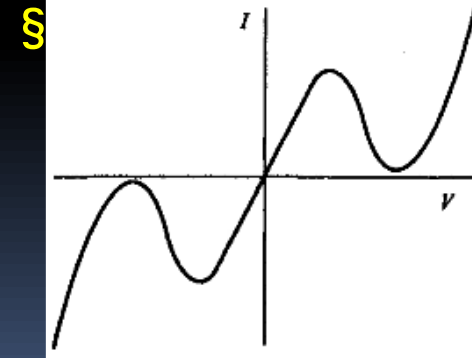
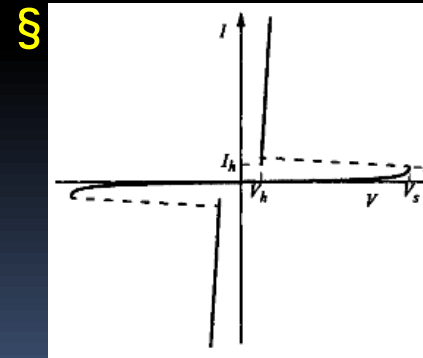
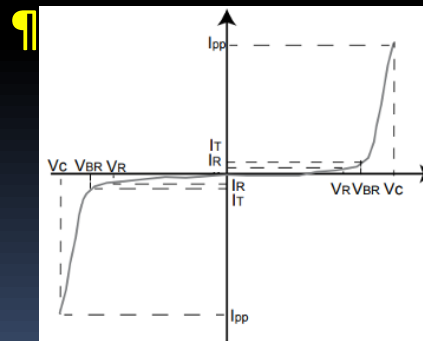


S-Shape



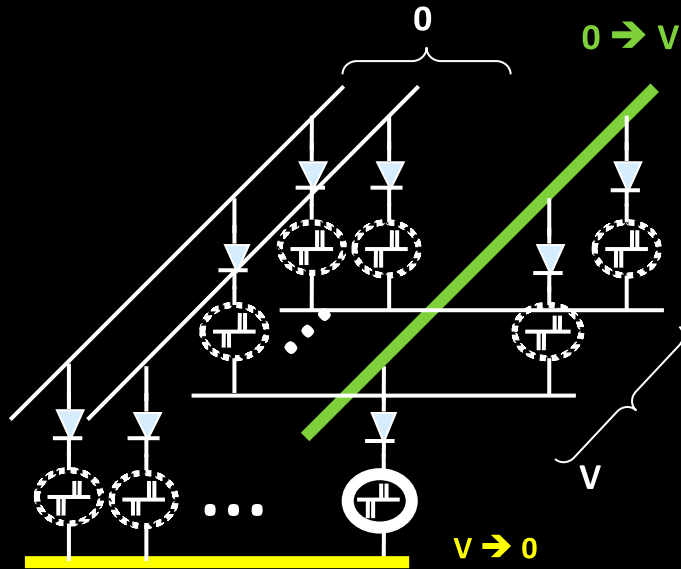
N-Shape

Bidirectional  
Symmetric  
Ambipolar



# Random Access of a Memory in Cross Point Array

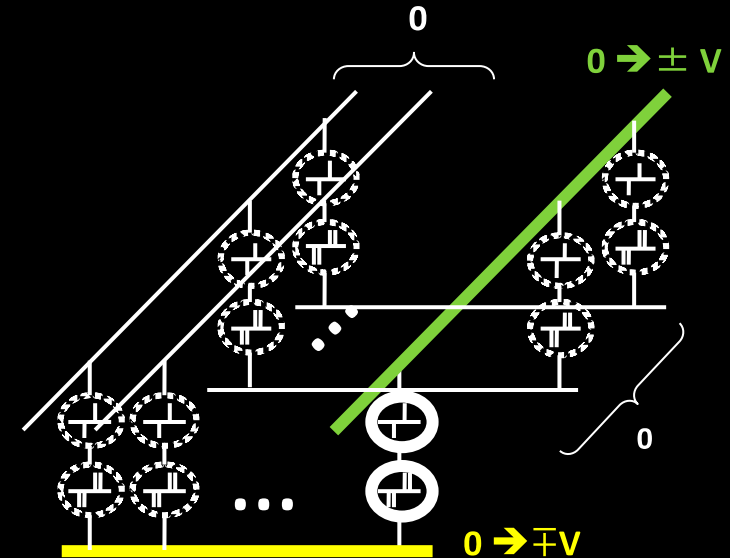
## Unidirectional L-Shape Selector



A rectifying selector turns on one bit with forward bias and isolates others with reverse bias.

- Selected BL/WL are toggled between  $0V$  and  $V$
- All bits but selected WL/BL are reversed biased

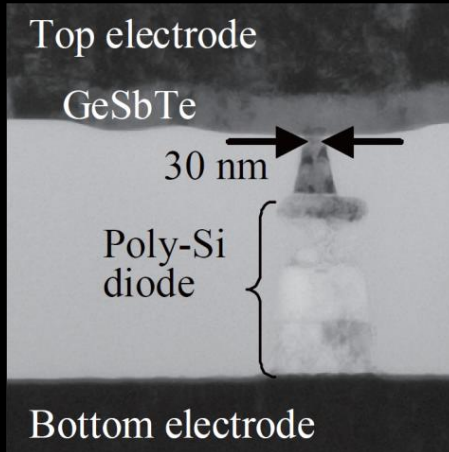
## Bidirectional S-Shape Selector



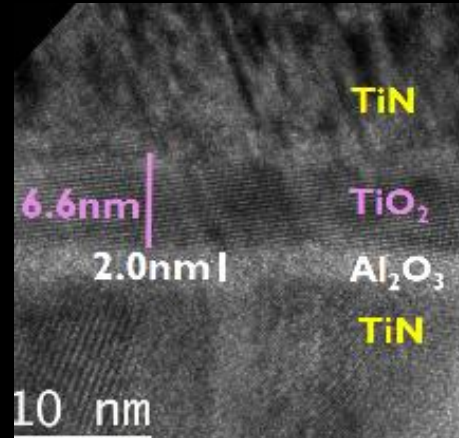
Subject to  $V_{\text{drop}}$  at each cross points, the selected bit is triggered, and the unselected bits are blocked.

- Selected BL/WL are toggled between  $0V$  and  $\pm V$
- All bits but selected WL/BL are  $0$  biased

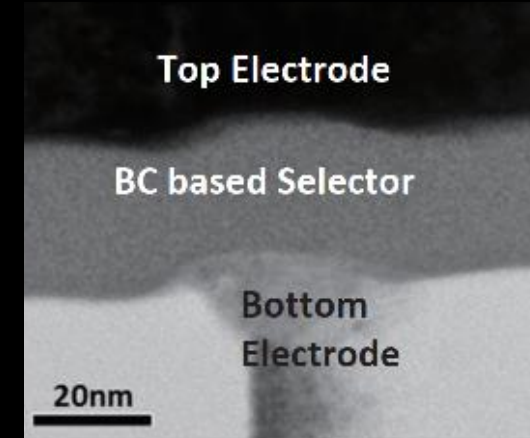
# Thin Film Diode Candidates for Cross Point Memory



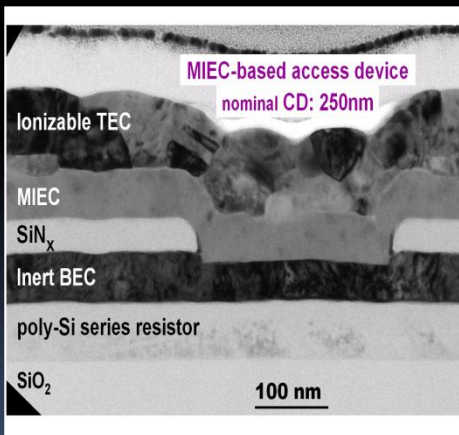
Y. Sasago, *et. al.*,  
VLSI '09. T2B-1



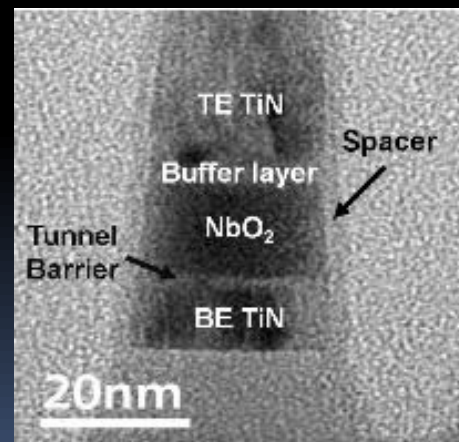
B. Govoreanu, *et.al.*,  
IEDM'13. S10.2



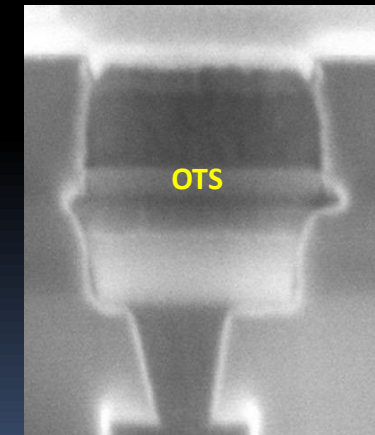
S. Yasuda, *et.al.*,  
VLSI, 2017. T2-4



K. Gopalakrishnan, *et. al.*,  
VLSI '10. TS19.41

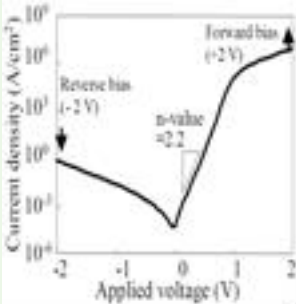
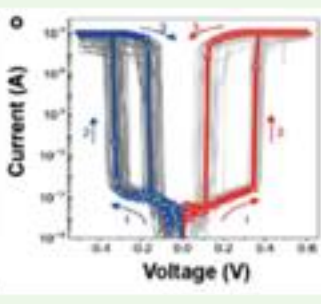
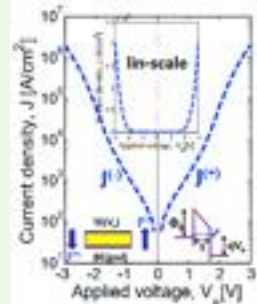
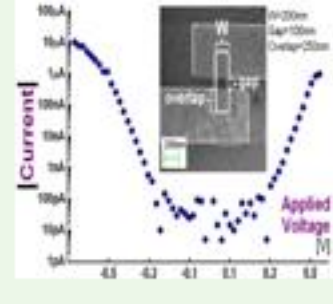
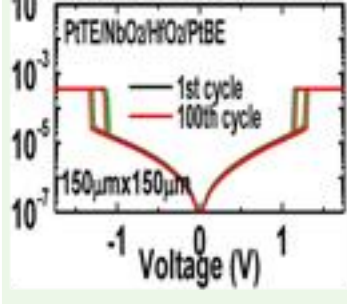
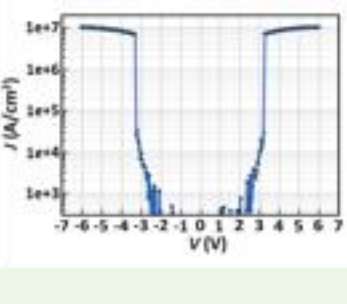


S.G. Kim, *et. al.*,  
IEDM '15. S10.3



D. Kau, *et. al.*,  
IEDM '09. S27.1

# Threshold Switching Phenomenology & Mechanisms

| Mechanism              | Thermionic   | Filamentation   | Tunneling  | MIEC   | MIT  | OTS  |
|------------------------|--|---|--|--|--|--|
| Construct.             | P-N or M-S Jx  | Ion ( $\text{Ag}^+$ ) in Ox   | MIM  | $\text{Cu}^+$ in SE  | $\text{NbO}_2$   | Chalcogenide   |
| Switching              | Electronic   | Atomistic   | Electronic   | Atomistic  | Atomistic  | Electronic   |
| Polarity               | Unidirectional   | Bidirectional   | Bidirectional  | Bidirectional  | Bidirectional  | Bidirectional  |
| $\tau_{\text{switch}}$ | sub nsec   | ns ~ 100s ns  | ps or faster   | ns ~ 100s ns   | ns to 10s ns   | sub ns   |
| $J_{\text{MAX}}$       | $< 10\text{MA}/\text{cm}^2$  | $1\text{-}10\text{MA}/\text{cm}^2$  | $< 1\text{MA}/\text{cm}^2$   | $\sim 10\text{MA}/\text{cm}^2$   | $> 10\text{MA}/\text{cm}^2$  | $> 10\text{MA}/\text{cm}^2$  |
| $J_{\text{Inhibit}}$   | $< 1\text{A}/\text{cm}^2$  | $< 1\text{KA}/\text{cm}^2$  | $< 1\text{KA}/\text{cm}^2$   | $< 1\text{KA}/\text{cm}^2$   | $< 1\text{KA}/\text{cm}^2$   | $< 1\text{KA}/\text{cm}^2$   |
| $V_{\text{Inhibit}}$   | $< 3\text{V}$  | $< 1\text{V}$   | $< 3\text{V}$  | $< 1\text{V}$  | $< 3\text{V}$  | $< 3\text{V}$  |
| I-V                    |  |  |  |  |  |  |
| Reference              | Y. Sasago, <i>et. al.</i> , VLSI '09   | Z. Wang, <i>et.al.</i> , Adv Func Mtls (2018)                                       | B. Govoreanu, <i>et.al.</i> , IEDM'13. P10.2   | K. Gopalakrishnan, <i>et.al.</i> , VLSI Symposium '10.                               | X. Liu <i>et.al.</i> , EDL Oct.'14   | S. Yasuda, <i>et.al.</i> , VLSI symposium, '17,                                      |

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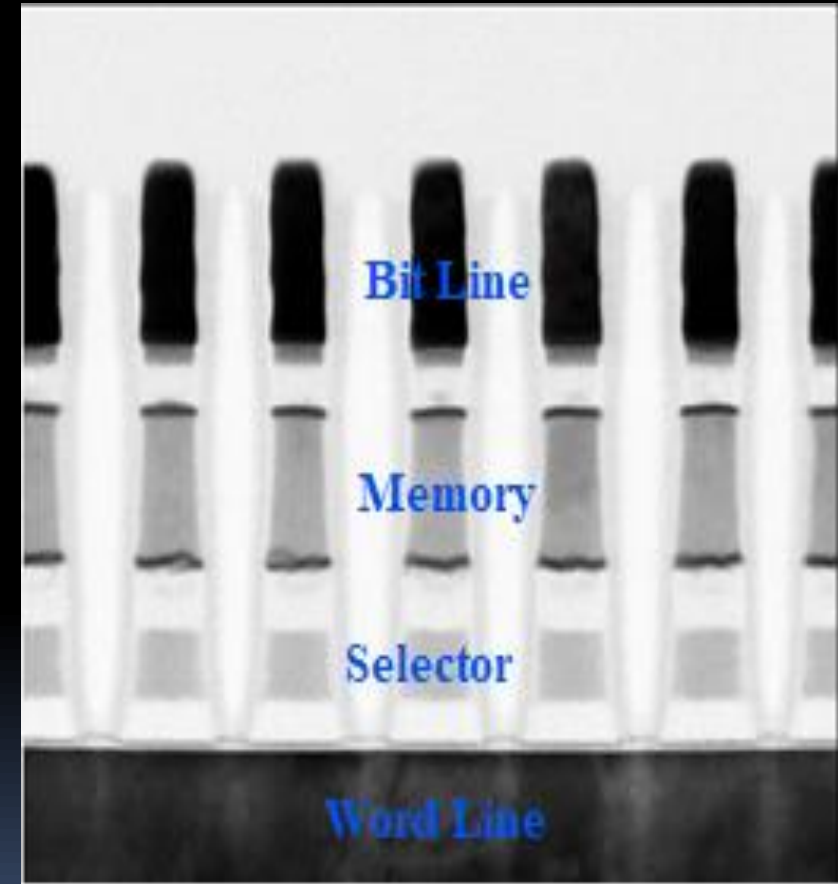
# Memory Cell

Sandwiched at the cross point of wordline and bitline metals

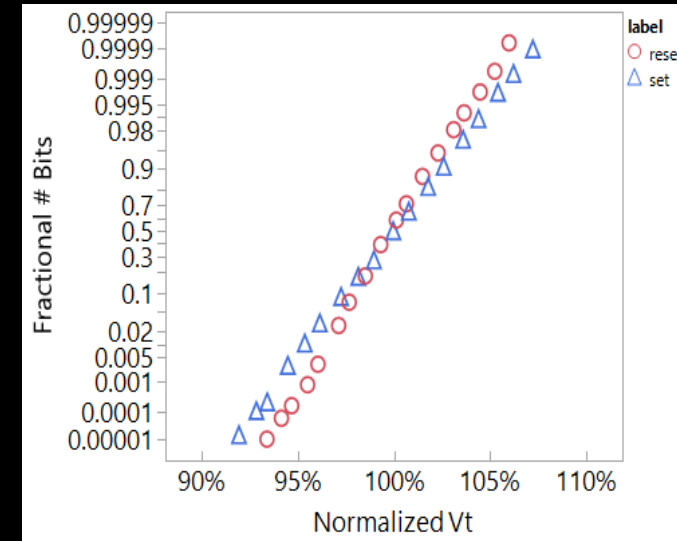
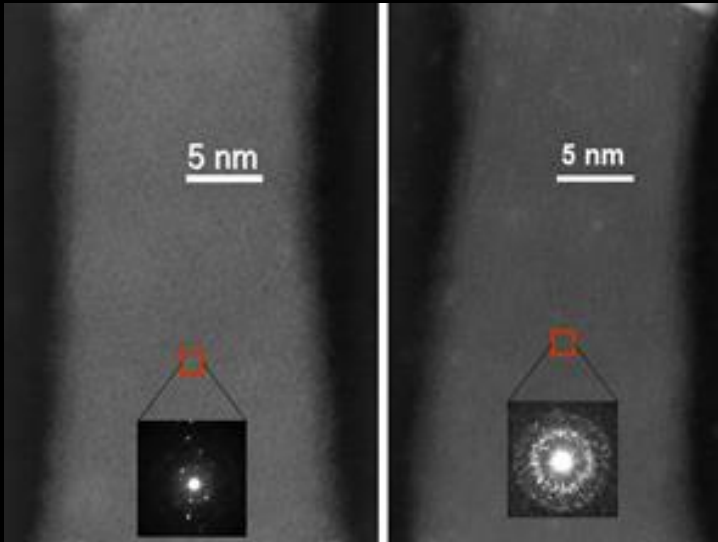
Selector device is based on Ovonic threshold switches

Storage element is based on chalcogenide alloy with power efficient memory switching without sub-lithography feature

Carbon electrode has two jobs: electrical connector and chemical barrier



# Memory Switching



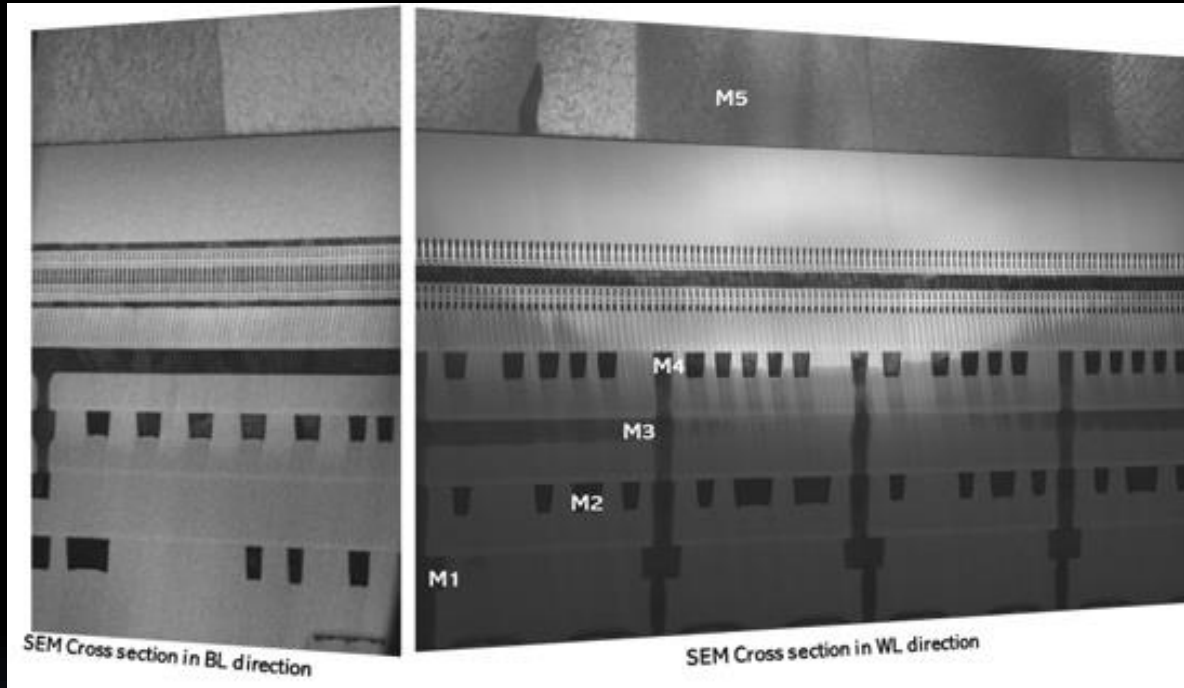
## Distinct bulk switching in departure from prevalent chalcogenide memory

**Tight statistical control:** The entire volume of memory material undergoes bonding transformations between high (fully crystalline) and low (fully amorphous) conductivity with no partial switching.

**Deterministic write algorithms:** While it shares a chalcogenide-based genealogy with PCM, it does not rely on stochastic crystallization growth processes initiated at the amorphous-crystalline interface no program verification is required.

**These fundamental architectural advantages enable low latency, high bandwidth, AND high endurance NVM subsystems.**

# High-Volume Manufacturing Proven



| 1st Generation 3D XPoint Media Attributes |                     |
|---|---------------------|
| Attribute                                 | Value               |
| Cell Feature Size (half pitch)            | 20nm                |
| # Decks                                   | 2                   |
| Die Capacity                              | 128 Gbits           |
| Bank Access Size                          | 16 Bytes            |
| # Independent Banks                       | 16                  |
| Read Latency per Bank                     | 100nSec             |
| Write Latency per Bank                    | 500nSec             |
| Write Bandwidth (MB/s) per TB             | >35,000MByte/sec/TB |

First generation 128Gb 3D XPoint Memory featuring 5-level metal CMOS Under Array technology delivers high density, low latency nonvolatile memory.

# Scaling Direction

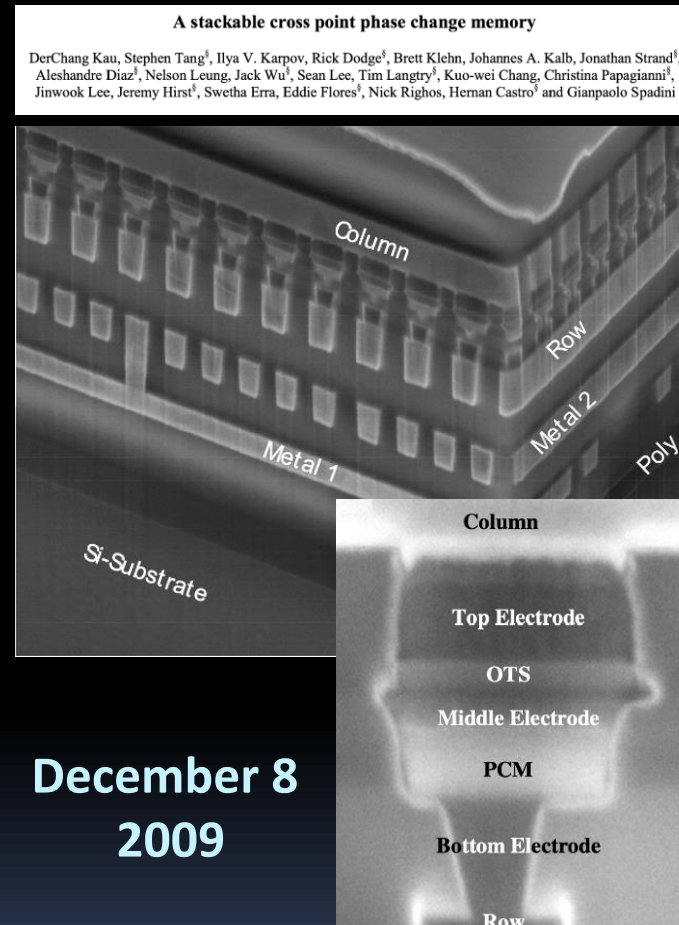
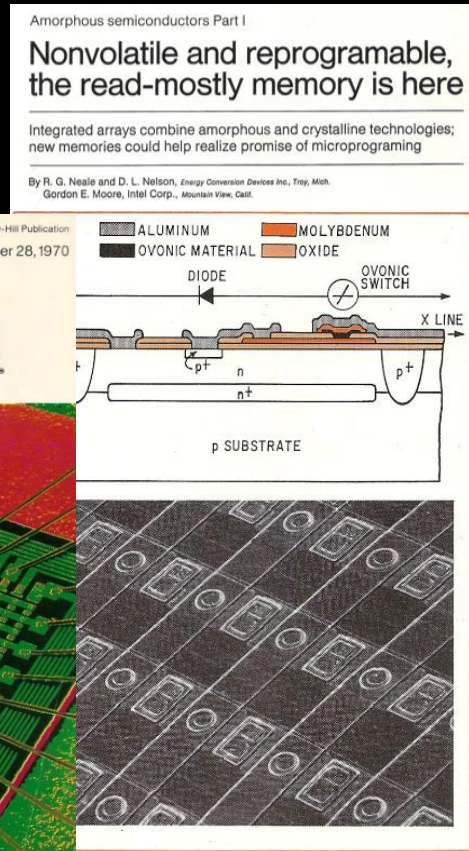
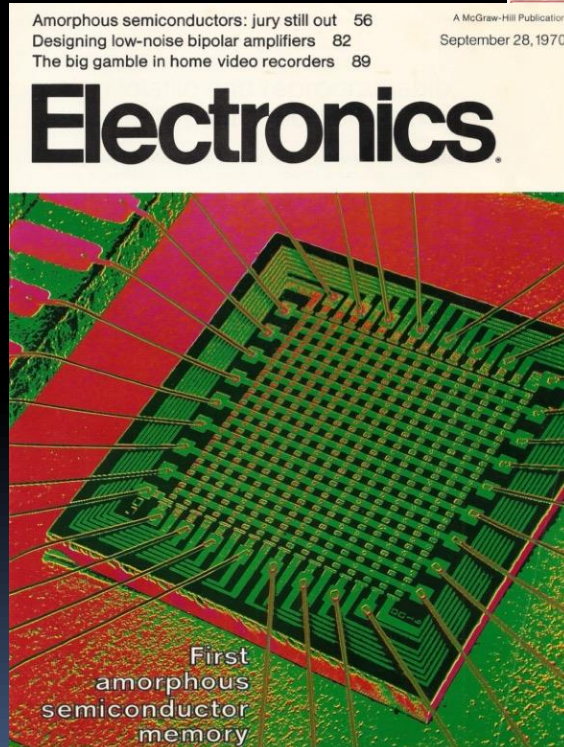
- Physical Scaling (Density)
  - Increase deck count → Vertical scaling
  - Pitch reduction → Lateral scaling
- Energy scaling
  - Variation tightening for supply reduction
  - Circuit efficiency improvement to reduce AC and DC dissipation
- BW scaling
  - Protocol and circuit optimization to reduce access latency
  - Increase bank count for concurrency
  - Material tuning for performance improvement
- Flash inspired (NOR and NAND)
  - Multi-Level Cell
  - Architecture augmentation

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# In Pursuit of a Dream ...

September 28  
1970



December 8  
2009

August 13  
2020

## A Half Century Endeavor



# 3D XPoint Technology Bridges Memory-Storage Gap

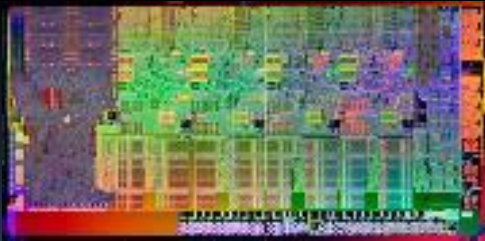
## MEMORY

+

## STORAGE

### SRAM

Latency: 1X  
Capacity: 1X



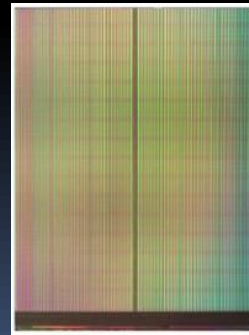
### DRAM

Latency: ~10X  
Capacity: ~100X



### 3D XPoint

Latency: ~100X  
Capacity: ~1,000X



### NAND SSD

Latency: ~100,000X  
Capacity: ~4,000X-8,000X

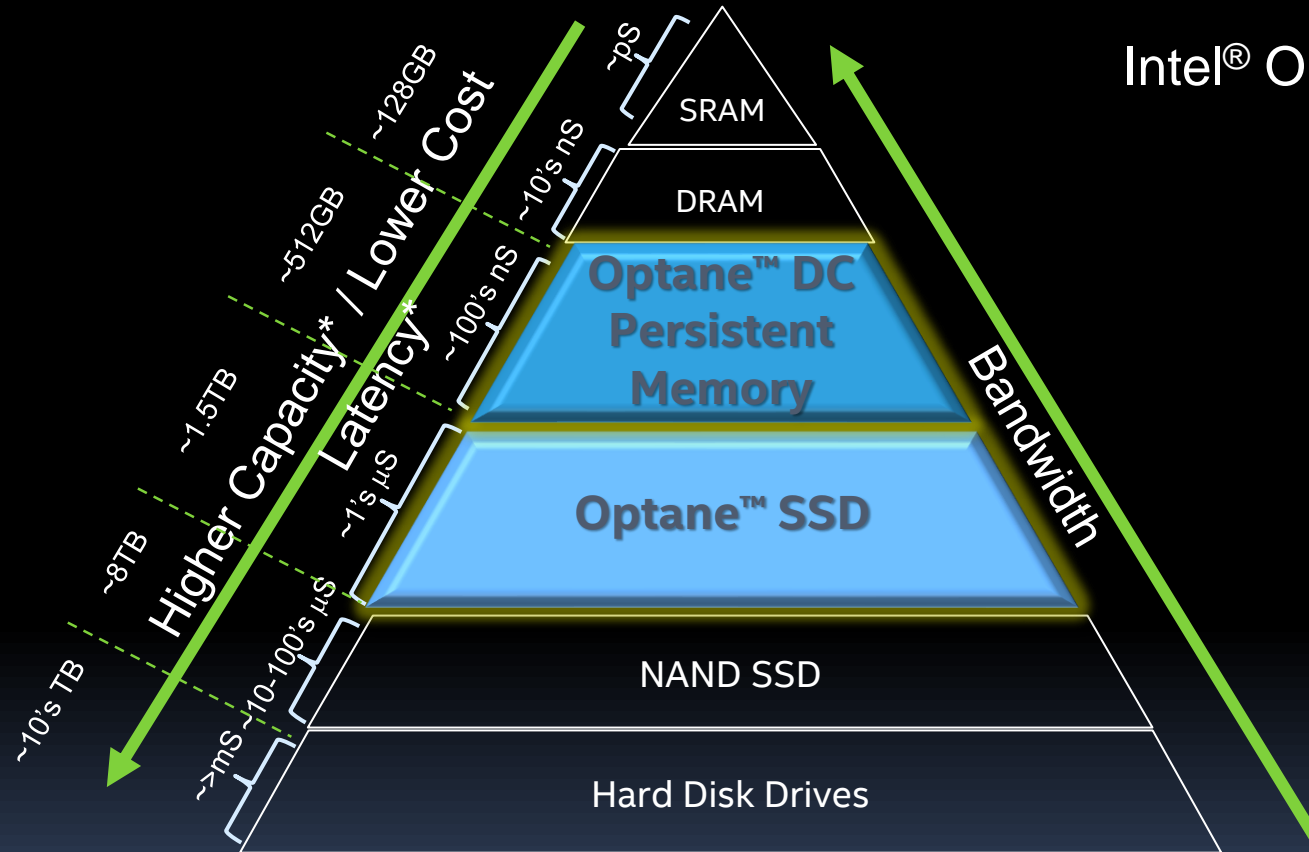


### HDD

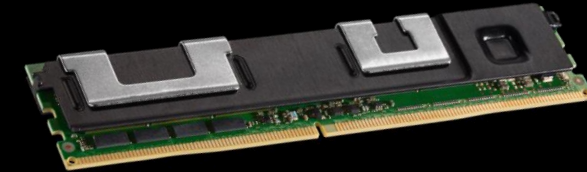
Latency: ~10 Million X  
Capacity: ~10,000X



# Optane™ based on 3D XPoint



Intel® Optane™ Data Center Persistent Memory



Intel® Optane™ SSD's





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